



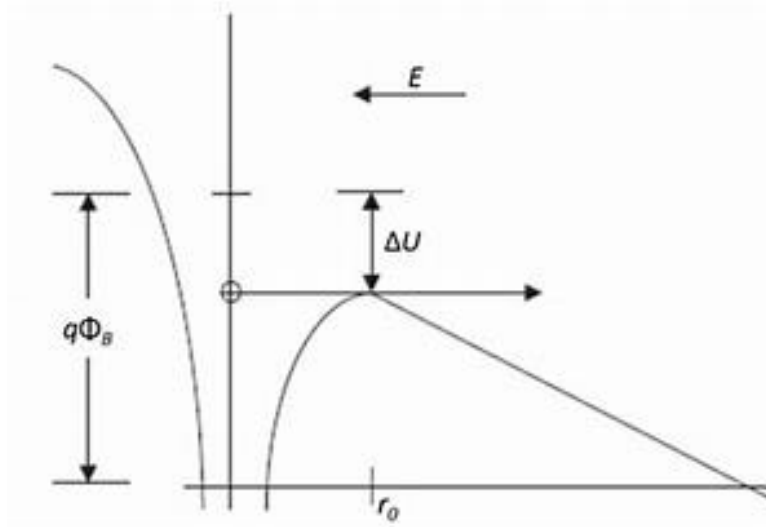
a YAGEO company

Derating and Technology in Polymer Tantalum Capacitors

Y. Freeman and P. Lessner

Leakage Current and Electric Field

Poole-Frenkel Conduction



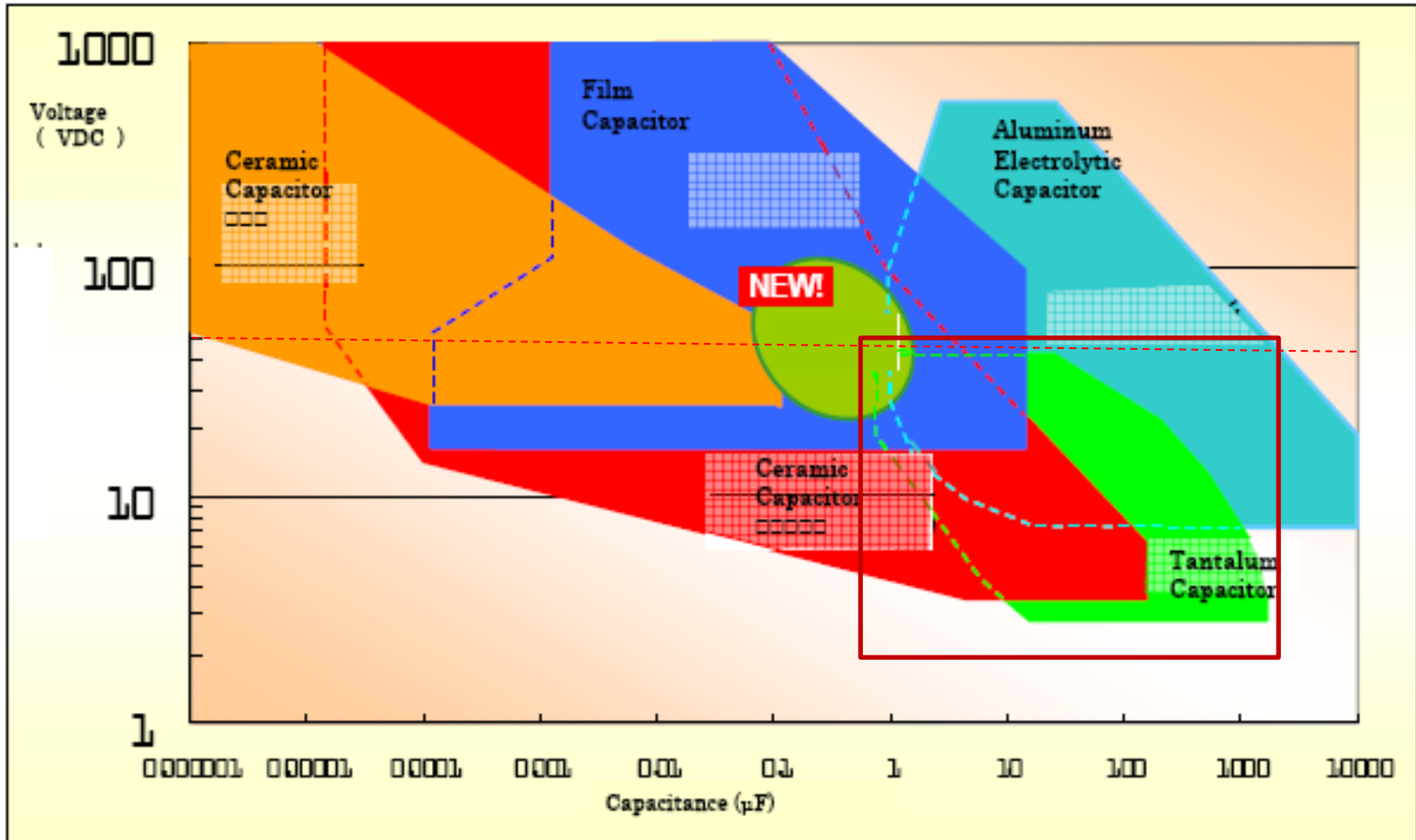
$$J \propto E \exp\left(\frac{q\sqrt{qE}/(\pi\epsilon)}{k_B T}\right)$$

$$E = V_a/d$$

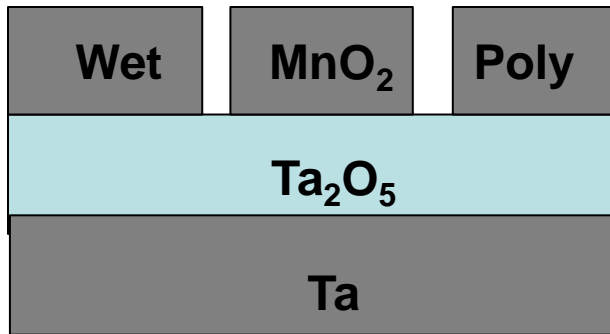
V_a – applied voltage
 d – dielectric thickness



Capacitor World (Murata 2000)



Evolution of Ta Capacitors



+

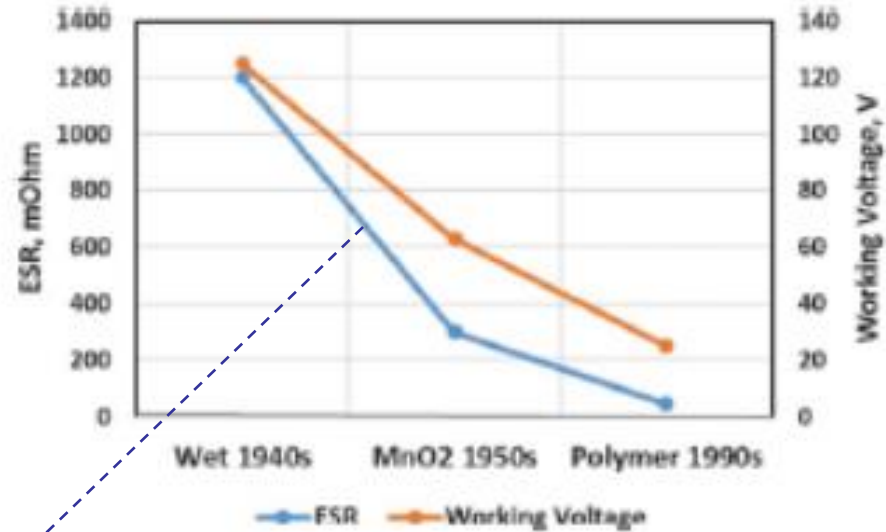
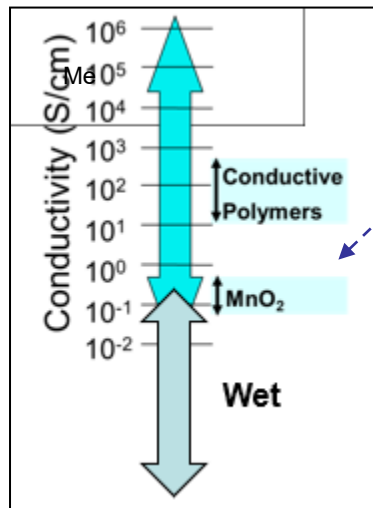


Fig. 4 ESR and maximum working voltage in different types of tantalum capacitors



Ignition Failure Mode

Solid Electrolytic Ta Capacitors



rated voltage reversed

All Solid Ta Capacitors

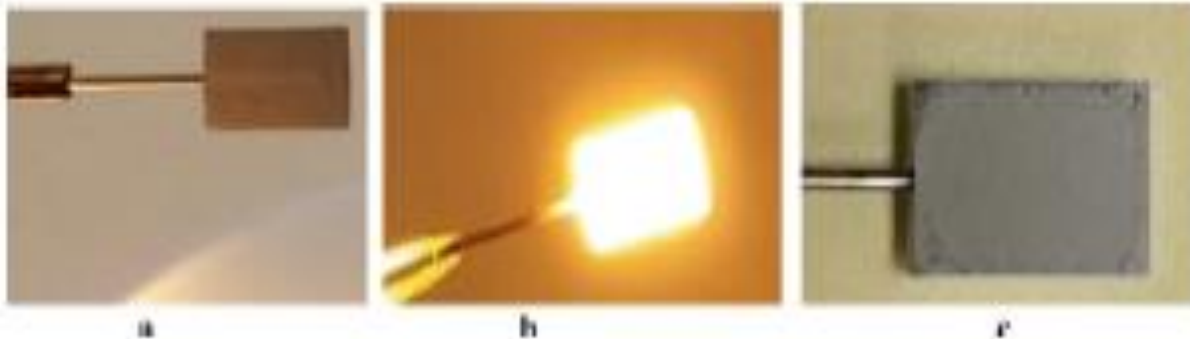


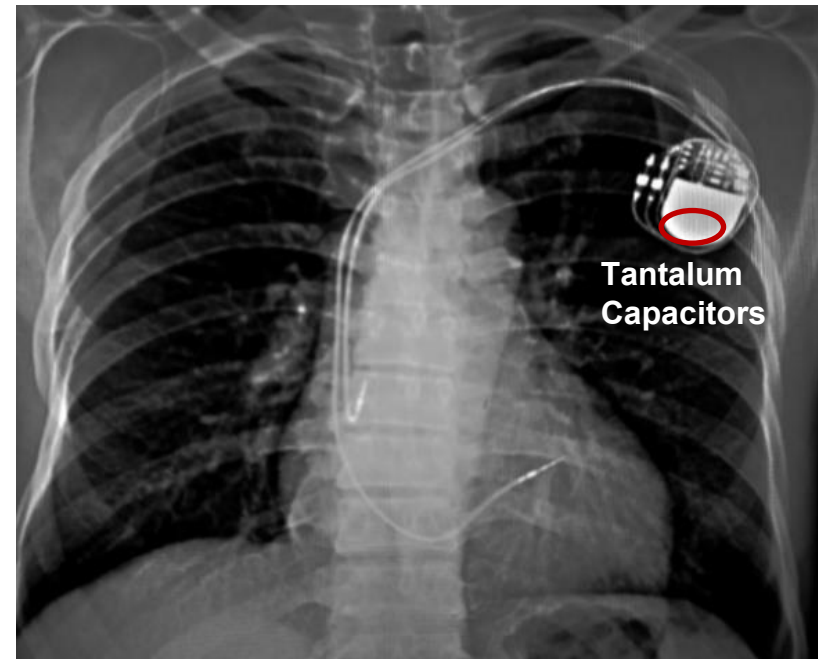
Fig. 3.27 Tantalum anode ignited with a burner (a), burning (b) and cooled to room temperature (c)

Volumetric Efficiency

Stationary defibrillator



ICD



Wikipedia



Volumetric Efficiency and Derating

C~A/d

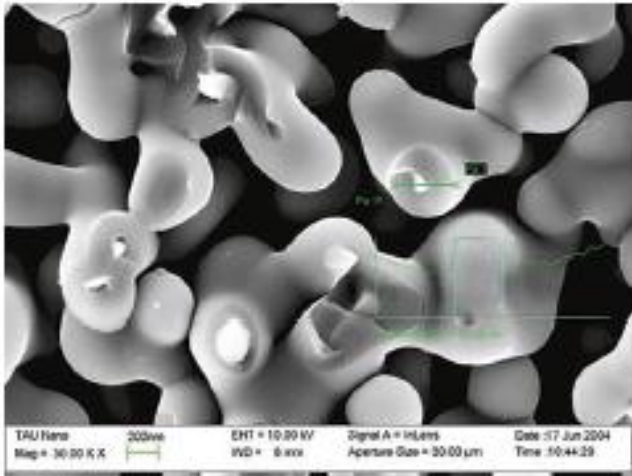


Fig. 3.3 Breakage of the tantalum anode sintered with 50,000 µC/g tantalum powder and formed to 75 V

50% Derating

Fig. 3.16 Solid Electrolytic Tantalum capacitors: D-case 4.7 µF, 50 V (left), and A-case 4.7 µF, 25 V (right)



increased
volume,
weight,
cost



Effect of Dielectric Thickness

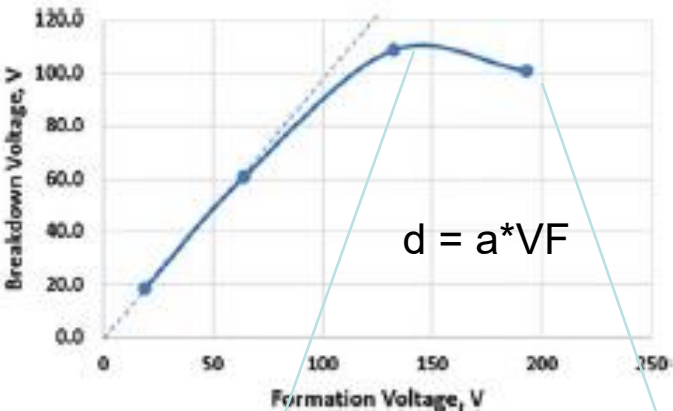


Fig. 3.18 Breakdown voltage dependence on formation voltage in Solid Electrolytic Tantalum capacitors

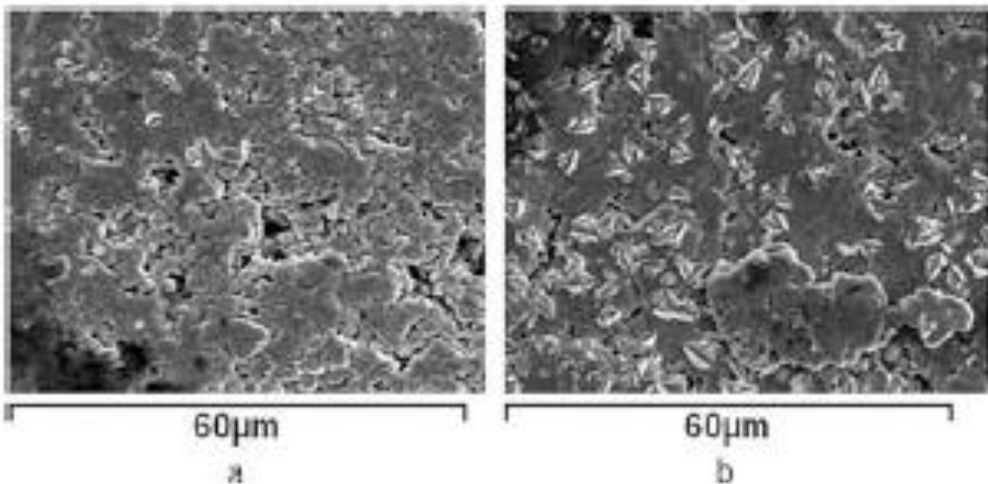


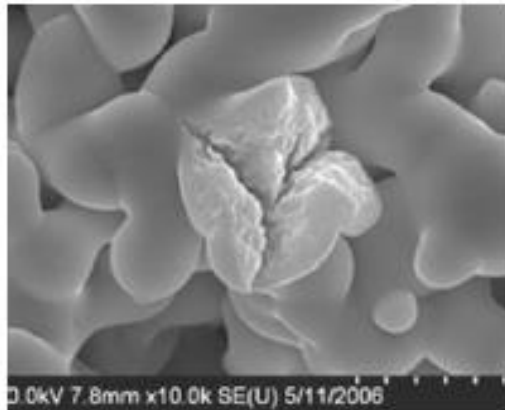
Fig. 3.17 SEM images of tantalum anodes formed at formation voltages 130 V (a) and 190 V (b)



Crystallization and Flawless Dielectric Technology (F-Tech)

Conventional

Fig. 1.8 Cracks from a crystal growing in anodic oxide film on tantalum anode with critical oxygen content



F-Tech

Fig. 2.25 SEM image of flawless Ta₂O₅ dielectric formed on F-Tech tantalum anode

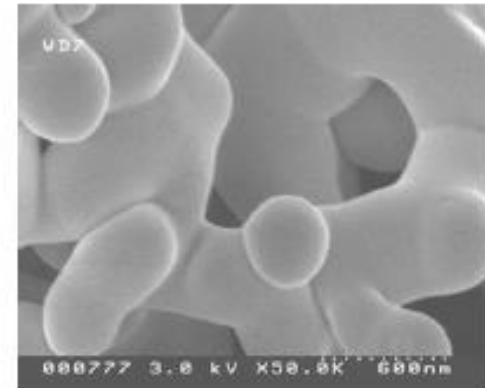
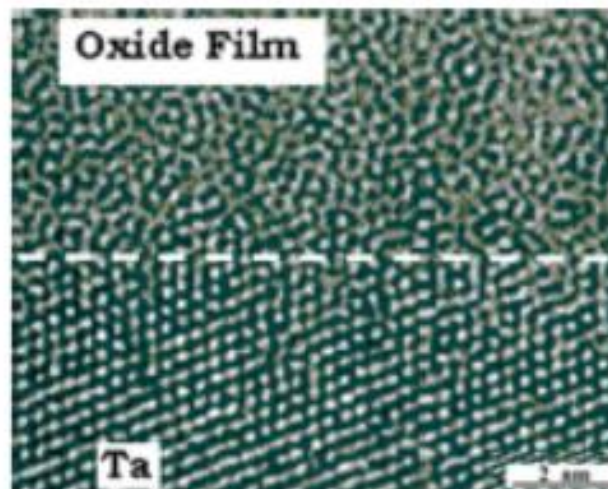


Fig. 1.2 TEM image of the amorphous anodic oxide film formed on crystalline tantalum (the white spots represent individual atoms)



Simulated Breakdown Screening (SBDS)

BDV Before/After SBDS

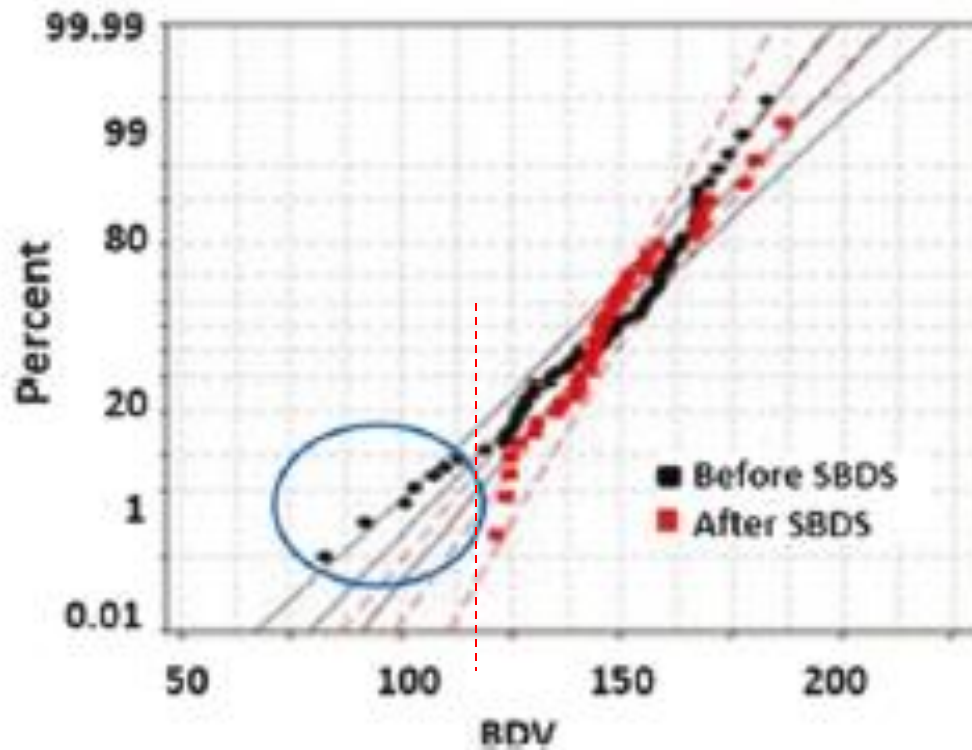


Fig. 2.33 BDV distributions in D-case 4.7 μF -50 V Solid Electrolytic Tantalum capacitors before and after SBDS



Customers on F-Tech/SBDS and Advantages of Lo/No De-rating

Northrop Grumman in Proceedings CARTS USA 2014
The F-TECH Process Demonstrated Improved Capacitor Failure Rate Versus "Standard" Processing

Industry average 0.1% lots	Industry average 1% lots	KEMET F-Tech/SBDS
1.65E-03	2.60E-03	3.64E-11

Time-to-failure for 1M parts:

8 months

12 months

- 5,000 years



Efficient, Reliable, and Cost Effective with Low/No Derating



No Ignition Failure Mode in Ta/MnO₂ Capacitors

“Burning Tantalum”

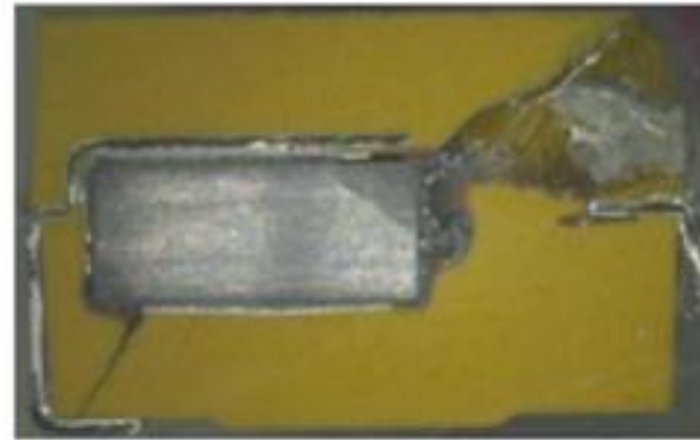
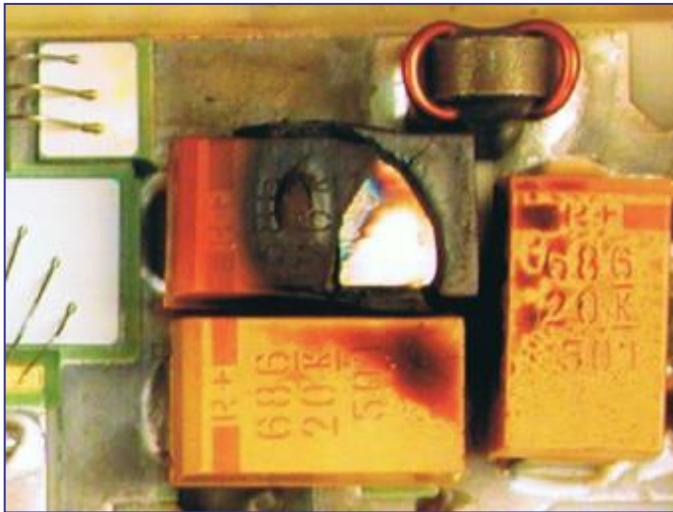


Fig. 3.28 Cross section of the failed short X-case 6.8 μ F, 50 V Solid Electrolytic Tantalum capacitor

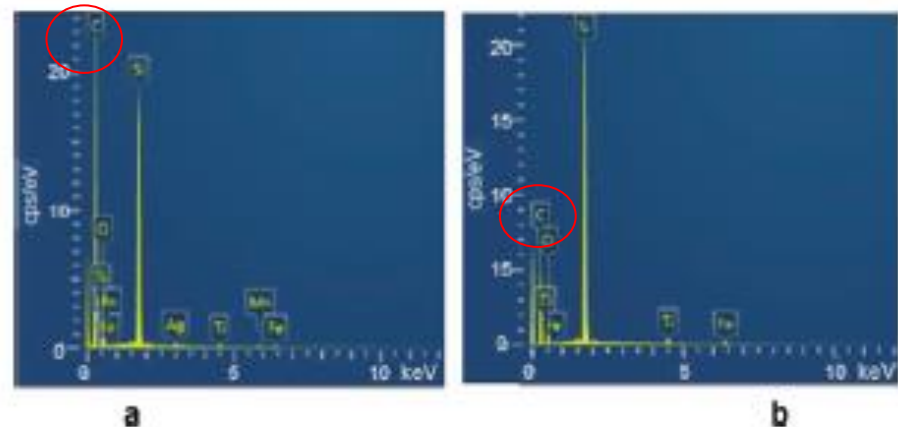


Fig. 3.29 EDX spectra of the epoxy compound inside (a) and outside (b) the black mark on the surface of the epoxy compound in failed short X-case 6.8 μ F, 50 V Solid Electrolytic Tantalum capacitor

Progress in Polymer Tantalum Capacitors (PTC)

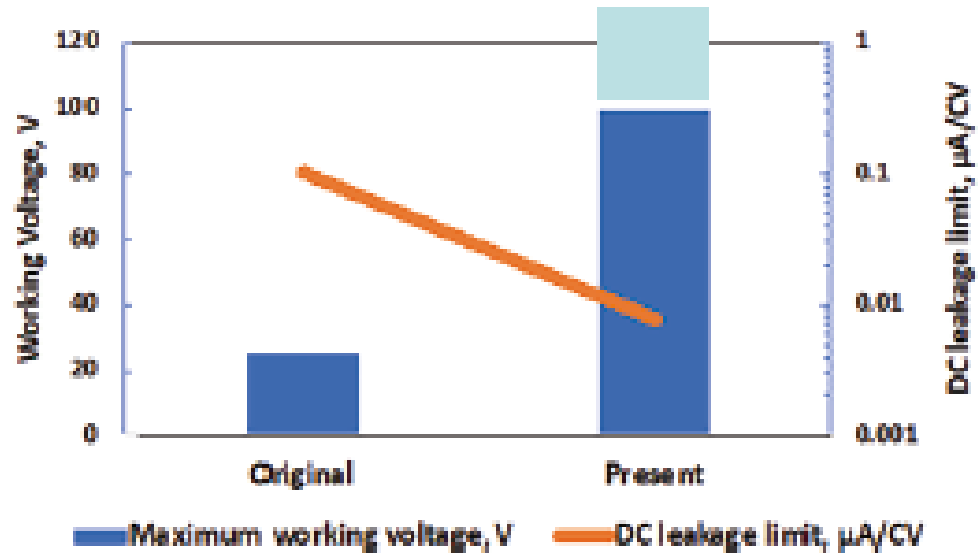
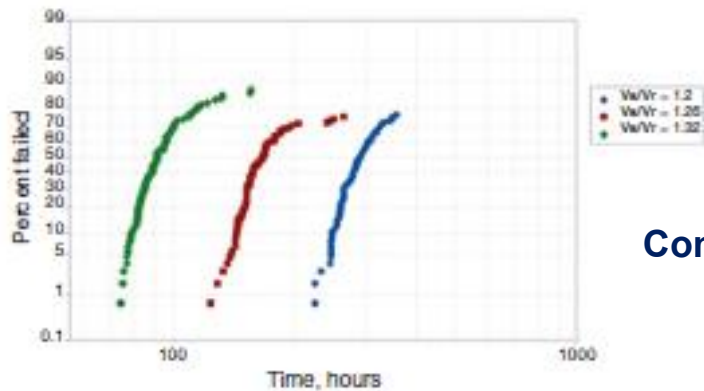


Fig. 3.31 Maximum working voltage and DC leakage per CV limit in Polymer Tantalum capacitors



No Wear-Out in PTC with F-Tech

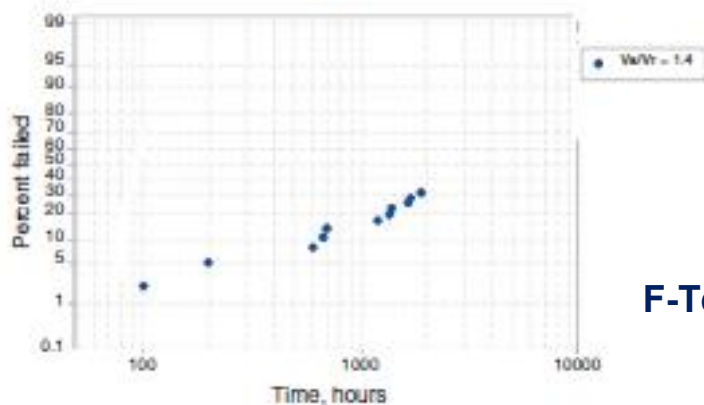


Conventional

$$A = A_V * A_T$$

A_V – Weibull equation

A_T – Arrhenius equation



F-Tech/SBDS

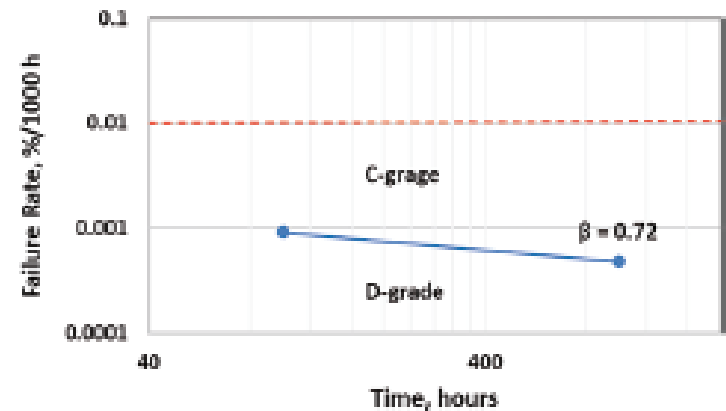


Fig. 3.20 Cumulative percent of failed parts versus time at accelerated test of H-case 220 µF, 25 V Polymer Tantalum capacitors manufactured with conventional technology (a) and F-Tech (b) at different V_t/V_r , and 105 °C

Fig. 3.21 Failure rate vs. time in H-case 220 µF, 25 V Polymer Tantalum capacitors manufactured with F-Tech and tested at $V_t/V_r = 1.4$ and 105 °C



Long-term Stability vs. Rated Voltage

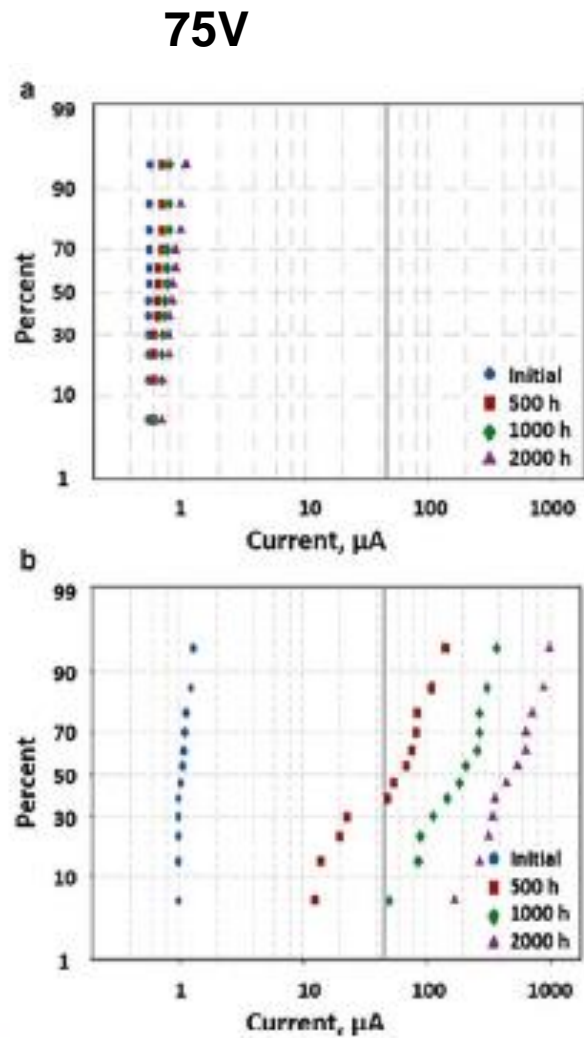


Fig. 3.40 DCL during life test at rated voltage and 85 °C in B-case 75 μ F-75 V humid (a) and dry (b) PHS Tantalum capacitors

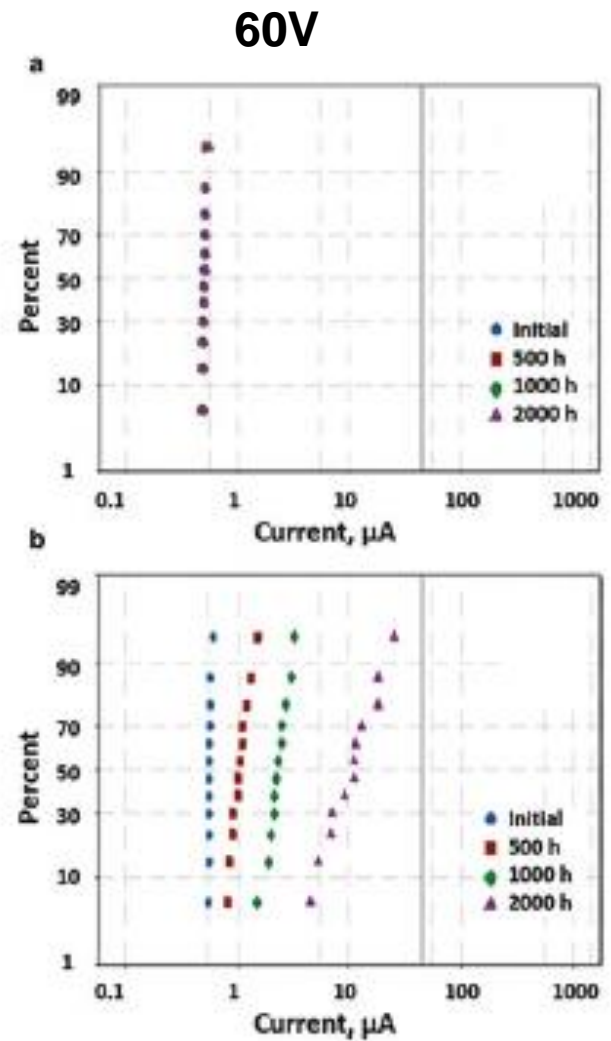


Fig. 3.42 DCL during life test at rated voltage and 85 °C in humid (a) and dry (b) B-case 100 μ F-60 V PHS Tantalum capacitors

Anomalous Charge Current (ACC) in Dry PTC

Effect of Polymer Cathode

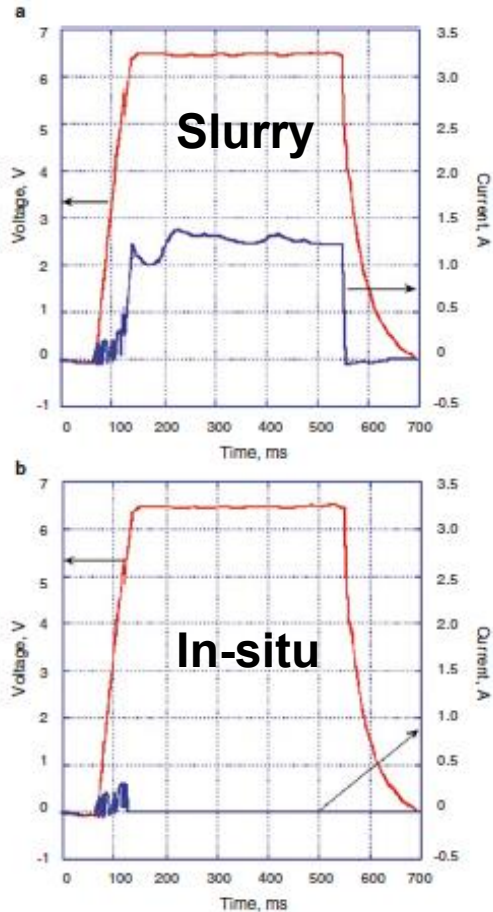


Fig. 3.61 $I(t)$ response to one pulse, $V(t)$, applied at $-200\text{ }^{\circ}\text{C}$ to a W-case $470\text{ }\mu\text{F}$ - 6.3 V hybrid (a) and pure in situ (b) Polymer Tantalum capacitors

Conventional vs. F-Tech

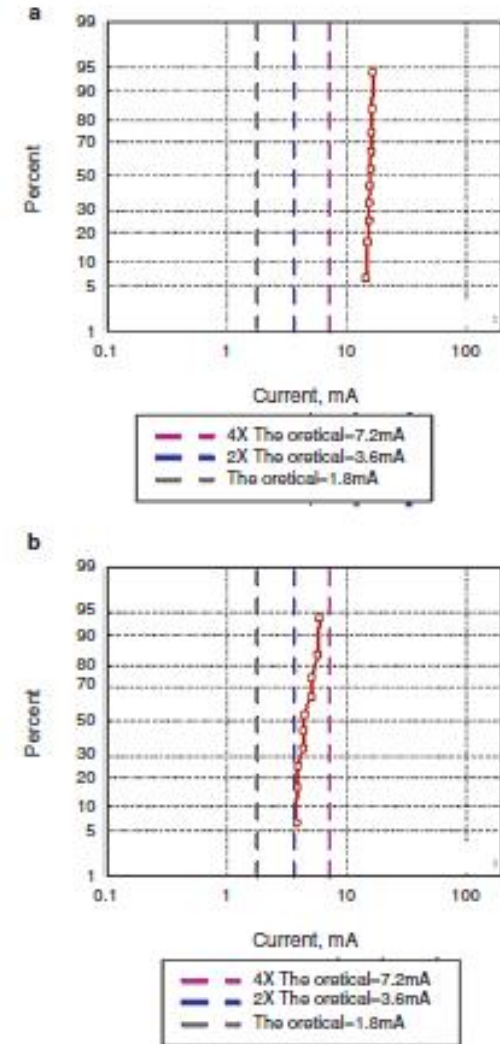


Fig. 3.64 Probability plots for the current distributions in D-case $15\text{ }\mu\text{F}$ - 35 V Polymer Tantalum capacitors with slurry PEDOT cathodes and either conventional dielectric technology (a) or F-Tech (b) charged to 28 V with a ramp of 120 V/s

Polymer Hermetic Seal (PHS) Ta Capacitors

(12) **United States Patent**
 Chen et al.

(10) **Patent No.:** US 8,379,371 B2
 (45) **Date of Patent:** Feb. 19, 2013

(54) **UTILIZATION OF MOISTURE IN HERMETICALLY SEALED SOLID ELECTROLYTIC CAPACITOR AND CAPACITORS MADE THEREOF**

(75) **Inventors:** Qingping Chen, Simpsonville, SC (US); Yuri Freeman, Greer, SC (US); Steven C. Hussey, Simpsonville, SC (US)

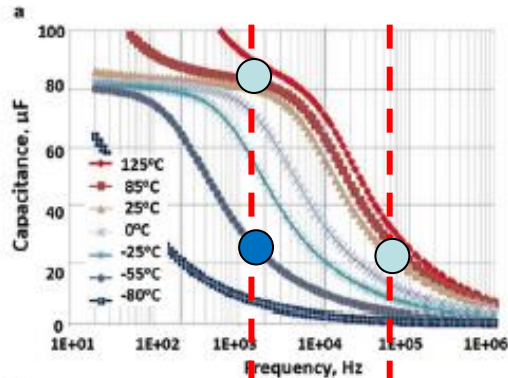
(73) **Assignee:** Kemet Electronics Corporation, Simpsonville, SC (US)

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C(f,T) in Wet and PHS B:82-75

Wets



PHS

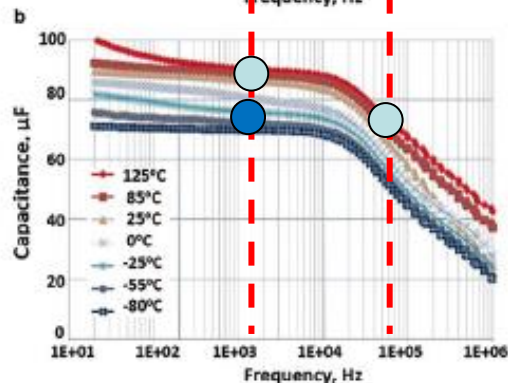


Fig. 3.37 Capacitance vs. frequency and temperature in B-case 82 μ F-75 V Wet (a) and PHS (b) tantalum capacitors

10,000h Life at 85C and RV

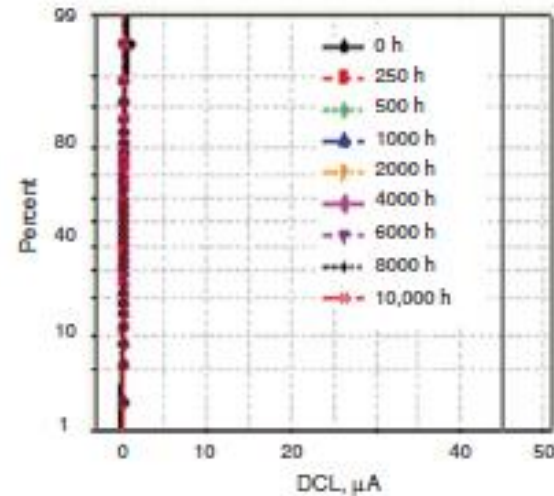
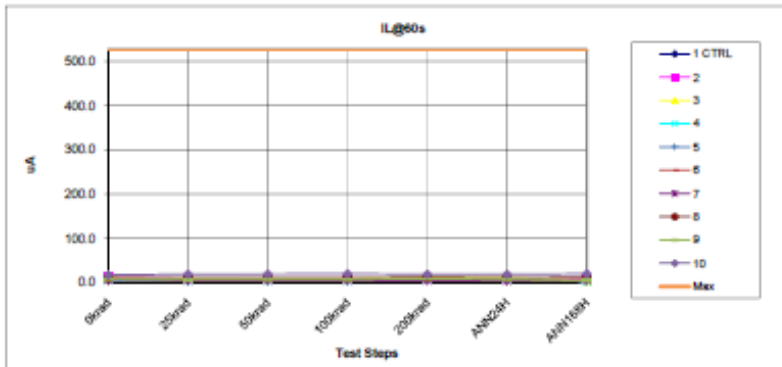
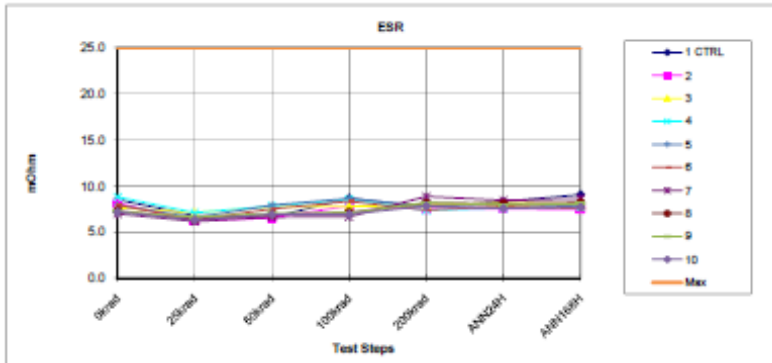


Fig. 3.35 DCL distributions in B-case 100 μ F-60 V PHS Tantalum capacitors during life test at rated voltage and 85 °C

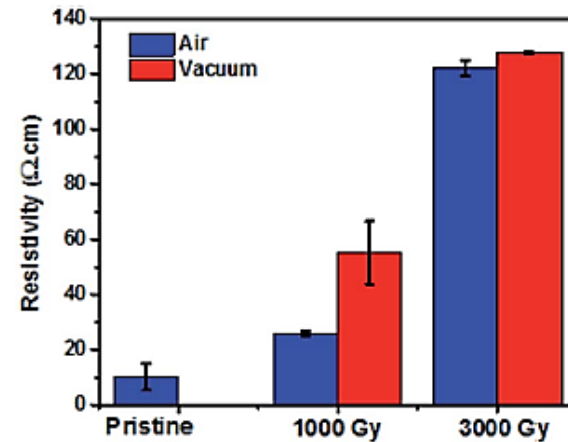


Effect of Radiation

Solid Electrolytic Ta Capacitors

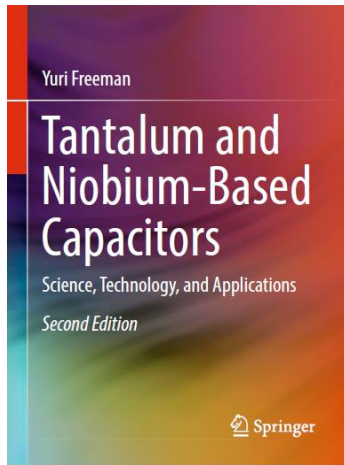


Cathode in Polymer Ta Capacitors



Resistivity as a function of dose for the PEDOT-PSS samples irradiated in air and vacuum [5]





Questions?

Consulting:

Science, Technology, and Applications of Tantalum Capacitors

Purpose:

Efficient, reliable and cost effective Ta solutions for your applications

Dr. Yuri Freeman

Ekeberg Prize and Tantalum Hall of Fame

E-mail: DoctorTantalum@gmail.com